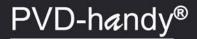


PVD-handy®





PRODUCT INFORMATION

Vaksis PVD – handy series is really convenient for use and easily handled as the adjective "handy" described in the dictionary which involves the techniques and combinations below:

CONFIGURATION MATRIX

Techniques	Magnetron Sputtering (MS)	Thermal Evaporation (Th E)	Organic and Metal Evaporation (OLED/OPV)	Multi Tech.
PVD-handy	1	4	4	MS, Th E, e-Beam, OLED/OPV

TECHNICAL SPECIFICATIONS

Base Pressure	≈ 2x10 ⁻⁷ Torr
Substrate Size	max. 4" diameter
Substrate Heating	max. 500°C
Substrate Rotation	10 rpm
Thickness Measurement	In-situ measurement with Quartz X-tal Oscillator
Temperature Controlling System	PID method
Loading	From the swing open bell jar

POWER SOURCES

- -DC and/or RF Power Supply for Sputtering Magnetron Source
- -Effusion Cell A.C. Power Supply for Metal and/or Organic Evaporation Sources
- -High-Current Low-Voltage A.C. Power Supply for Resistive Thermal Evaporation Source

SOFTWARE

System operation by user-friendly software. It is not only the automation and control software but also coating management software which allows the user design his/her specific coating experiments, examine the process parameters used in the past, and use the recipes/coatings developed in the past without hustle.

Human and machine safeties are prime importance in the operations performed by the software. A graphical user interface will allow the user to see the status of the system during operation.

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